

L Number	Hits	Search Text	DB	Time stamp
1	2	("4659960").PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:05
2	0	445/7.ccls. and ((cvd pvd) with (vapor vapour))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:06
3	0	445/7.ccls. and ((cvd pvd) same (vapor vapour))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:06
4	44111	((cvd pvd) with (vapor vapour))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:06
5	0	313/118.ccls. and ((cvd pvd) with (vapor vapour))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:07
6	133910	"vapor deposition"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:07
7	0	445/7.ccls. and "vapor deposition"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:07
8	3	313/118.ccls. and "vapor deposition"	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:08
9	750	313/\$.ccls. and ("vapor deposition" same (cvd pvd))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:08
10	1	313/137,143.ccls. and ("vapor deposition" same (cvd pvd))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:10
11	1	445/7.ccls. and (coat\$3 same suspension)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:12
12	0	445/7.ccls. and ((cvd pvd sputter\$3 plat\$3 evaporat\$3) same (stir\$4 and suspension\$))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:13
13	0	313/118,137,143,128,129,130,131a,141;123/169r,169el.ccls. and ((cvd pvd sputter\$3 plat\$3 evaporat\$3) same (stir\$4 and suspension\$))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:14
14	0	(313/118,137,143,128,129,130,131a,141.ccls. or 123/169r,169el.ccls.) and ((cvd pvd sputter\$3 plat\$3 evaporat\$3) same (stir\$4 and suspension\$))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:15
15	35492	(cvd pvd sputter\$3 plat\$3 evaporat\$3) same (stir\$4 and suspension\$)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:16
16	8	((cvd pvd sputter\$3 plat\$3 evaporat\$3) same (stir\$4 and suspension\$)) and (spark near2 plug)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:18
17	3858	((cvd pvd sputter\$3 plated plating evaporat\$3) same (stir stirring stirred and suspension\$)) and (coat\$3 near4 (particle\$ granule\$ grain\$))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:19

18	819	((cvd pvd sputter\$3 plated plating evaporat\$3) same (stir stirring stirred and suspension\$)) and (coat\$3 near4 (particle\$ granule\$ grain\$))) and ((ceramic alumina) and (platinum pt metal noble))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:20
19	28	((cvd pvd sputter\$3 plated plating evaporat\$3) same (stir stirring stirred and suspension\$)) and (coat\$3 near4 (particle\$ granule\$ grain\$))) and (alumina same platinum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:26
20	70	((cvd pvd sputter\$3 plated plating evaporat\$3) same (stir stirring stirred and suspension\$)) and (coat\$3 near4 (particle\$ granule\$ grain\$))) and (organic adj binder)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:26
21	0	((cvd pvd sputter\$3 plated plating evaporat\$3) same (stir stirring stirred and suspension\$)) and (coat\$3 near4 (particle\$ granule\$ grain\$))) and (organic adj binder)) and cermet	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:27
22	70	((cvd pvd sputter\$3 plated plating evaporat\$3) same (stir stirring stirred and suspension\$)) and (coat\$3 near4 (particle\$ granule\$ grain\$))) and (organic adj binder)) and coat\$3	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:27
23	7	((cvd pvd sputter\$3 plated plating evaporat\$3) same (stir stirring stirred and suspension\$)) and (coat\$3 near4 (particle\$ granule\$ grain\$))) and (organic adj binder)) and (alumina and platinum)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 11:27
-	8	445/7.ccls. and (insulator with (press\$3 and mold\$3))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/08/15 10:49